NANOCHEM® H/HP-Series Gas Purifiers

Features and Benefits

- Purification for all ultra-high purity applications
- Highest Lifetimes
- Best Impurity Removal Efficiencies
 - Removes critical contaminants to sub parts-per-billion level (< 0.1 ppb in inert gases)
- End-Point Detection available (H-Series)
- Enhances manufacturing process economy and improves equipment performance
- Provides consistently high purity gas under fluctuating inlet impurity conditions
- Improves component lifetime and reduces particle generation by removing moisture and volatile metals from corrosive gases
- No moving parts or power requirements
- Easy to operate
- Built-in 1-valve bypass
- Does not require heating or cooling
- Low overall cost of ownership
- Media refills available for all sizes
- Inlet and outlet springless diaphragm valves

Specifications

- All metal parts, Type 316L stainless steel, nickel and Elgiloy® valve diaphragm
- 0.003 µm particle filter with 99.999999% retention (PTFE or 316L SS)
- Internal surface finish < 15 μin R_a
- H-Series: Maximum allowable working pressure of 150 psig (1.13 MPa) with the fiber optic end-point detector or 500 psig (3.5 MPa) without detector
- HP-Series: Maximum allowable working pressure of 2850 psig (19.7 MPa)
- Maximum operating temperature of 70°C

Connections

• Female inlet and male outlet 1/4 inch VCR®-compatible face seal fittings

Options

- Fiber optic end-point detector indicates when it is time to replace the purifier (for non-corrosive gases only)
- Pneumatically-actuated diaphragm valves
- Manually or pneumatically-actuated bellows valves

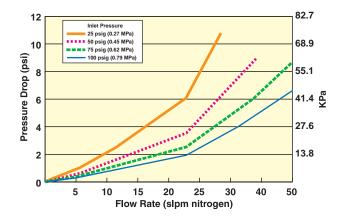
Description

The NANOCHEM® H/HP-Series Purifiers provide economical gas purification in multi-tool or single-source applications.

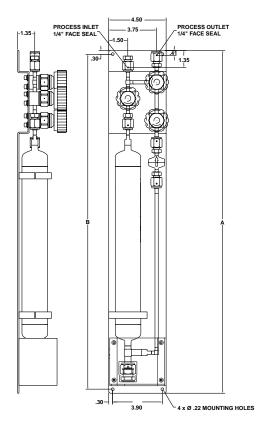
With a welded bypass valve incorporated in the purifier unit, H/HP-Series purifiers are often used in gas enclosures, both source and purge gas, where space is limited. Its low width makes it ideal for installation in restricted space or gas jungle applications where multiple vertical gas lines are being run.

Purification media refills are available through Matheson Tri-Gas, Inc.









Operating Pressure and Flow Rates				
	H-500	HP-500		
Maximum allowable working pressure, psig	500	2850		
MPa	3.5	19.7		
Maximum recommended flow rate slpm, N ₂	50	50		
NM³/hr, N₂	3	3		

H/HP-Series Purifier	H/HP-500	HP-300
А	26.90	21.09
	(683.26)	(535.68)
В	26.30	20.49
	(668.02)	(520.45)

Cas Time	Impunities Demoused
Gas Type	Impurities Removed
Nitrogen (N₂), Argon (Ar), other inerts	$< 0.1 \text{ ppb H}_2\text{O}, \text{O}_2, \text{CO}_2 \text{ LDL}$
	< 1 ppb CO*
	< 0.1 ppb NMHC (with OMX-Plus™) LDL
A ' . /NH I \	NO_x , SO_x , H_2S
Ammonia (NH₃)	< 0.1 ppb H ₂ O, O ₂ , CO ₂ in inert gas LDL
	< 1 ppb CO*
	< 45 ppb H ₂ O in ammonia LDL
611 (6111)	NH ₃ -CO ₂ complexes, SiH ₄ , Siloxanes, GeH ₄ , H ₂ S
Silane (SiH ₄)	< 0.1 ppb H ₂ O, O ₂ , CO ₂ LDL
	< 1 ppb CO*
	Chlorosilanes, disilane, siloxanes, arsine, phosphine
Arsine (AsH ₃), Phosphine (PH ₃)	< 0.1 ppb H ₂ O, O ₂ , CO ₂ LDL
	< 45 ppb H ₂ O in phosphine LDL
	< 75 ppb H ₂ O in arsine LDL
	CO, oxyacids $(H_xAs_yO_z, H_xP_yO_z)$
Hydrogen (H ₂), Methane CH ₄), Ethane (C ₂ H ₆), other HC	< 0.1 ppb H ₂ O, O ₂ , CO ₂ LDL
	< 1 ppb CO*
	NO _x , SO _x , H ₂ S
Sulfur Hexafluoride (SF₅), Carbon Tetrafluoride (CF₄),	< 0.1 ppb H ₂ O, O ₂ , CO ₂ in inert gas LDL
other fluorocarbons	< 10 ppb O ₂ , H ₂ O in sulfur hexafluoride LDL
Oxygen (O_2) , Carbon Dioxide (CO_2) , Nitrous Oxide (N_2O)	< 10 ppb H₂O
Carbon Monoxide (CO)	Metal Carbonyls: Fe, Ni
Corrosives (HCI, HBr, CI ₂ , SiH ₂ CI ₂ , SiHCI ₃ , BCI ₃)	< 1 ppb H ₂ O in inert gas
	< 100 ppb H ₂ O in HBr LDL
	< 150 ppb H₂O in HCl
	Volatile Metals: Fe, Mo, Cr, Ni, Mn, Ti
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LDL – Lower Detection Limit by State-of-the-Art Analytical Instrumentation

NMHC – Non-methane Hydrocarbons
*NOTE: CO is removed efficiently by OMX & OMX-Plus™ media at low flow rates (recommend ¹/₁₀ of normal flow rate)

For a detailed list of purification media and impurities removed, refer to the Purification Media Table in NANOCHEM® Purification Solutions Brochure.

